

2014 International Workshop on EUV Lithography

**June 23-27, 2014 ■ Makena Beach & Golf Resort
■ Maui, Hawaii ■**

Wednesday, June 25, 2014

Organized by



www.euvlitho.com

EUVL Workshop Steering Committee

Executive Steering Committee

David Attwood (LBNL)

Han-Ku Cho (Samsung)

Hiroo Kinoshita (Hyogo University)

Harry Levinson (GLOBALFOUNDRIES)

Kurt Ronse (IMEC)

Sam Sivakumar (Intel)

Tony Yen (TSMC)

Debbie Gustafson (Energetiq)

Ahmed Hassanein (Purdue University)

Clifford Henderson (Georgia Institute of Technology)

Winfred Kaiser (Carl Zeiss)

Jaehyun Kim (Dongjin Semichem)

Seong-Sue Kim (Samsung)

Eric Louis (FOM)

Hye-Keun Oh (Hanyang University)

Takahiro Kozawa (Osaka University)

Christof Krautschik (Intel)

Rainer Lebert (Bruker)

Changmoon Lim (Hynix)

Pawitter Mangat (GlobalFoundries)

Warren Montgomery (CNSE)

Patrick Naulleau (LBNL)

Katsunobu Nishihara (Osaka University)

Sushil Padiyar (AMAT)

Yuriy Platonov (RIT)

David Pui (University of Minnesota)

Martin Richardson (University of Central Florida)

Valentino Rigato (LNL-INFN)

David Ruzic (University of Illinois at Urbana-Champaign)

Regina Soufli (LLNL)

Serge Tedesco (CEA)

Takeo Watanabe (Hyogo University)

Sergey Zakharov (EPPRA)

Technical Steering Committee

Jinho Ahn (Hanyang University)

Vadim Banine (ASML)

Davide Bleiner (University of Berne)

Alek Chen (ASML-Taiwan)

Ndaona Chokani (ETHZ)

Dan Corliss (IBM)

Marc Corthout (Xtreme)

Gregory Denbeaux (University of Albany)

Padraig Dunne (University College Dublin)

Samir Ellwi (Adlyte)

Akira Endo (Waseda University, Japan)

Masayuki Endo (Panasonic)

Torsten Feigl (Fraunhofer IOF)

Gregg Gallatin (NIST)

Mieke Goethals (IMEC)

Kenneth Goldberg (LBNL)

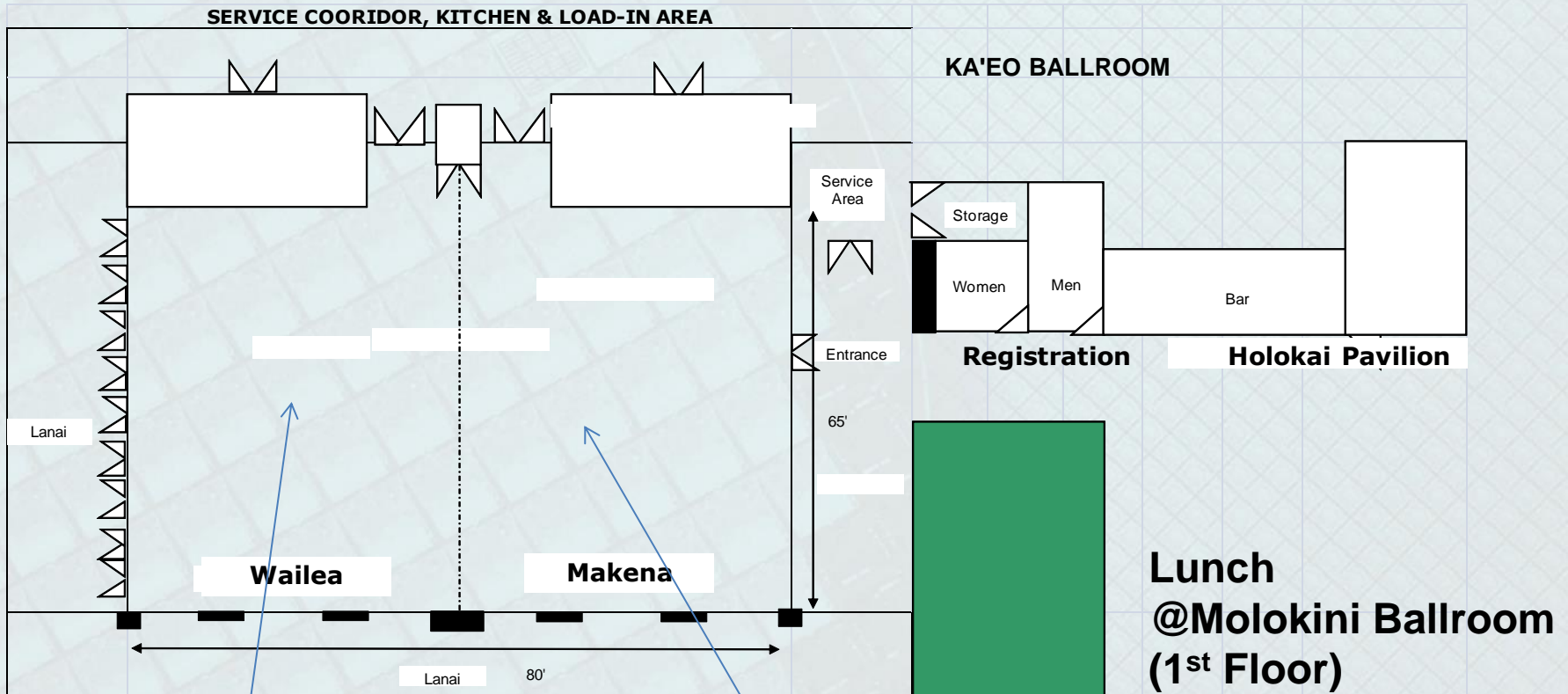
Steve Grantham (NIST)

2014 EUVL Workshop Sponsors



MAYOR'S OFFICE OF
ECONOMIC
DEVELOPMENT
MAUI COUNTY

Meeting Rooms: Makena Beach & Golf Resort



General Session

Poster Session

Announcements

- Speaker Timer – let us stay on time!
 - Green – OK
 - Yellow –Q&A time started
 - Red – Time Over
- Hand held reminder signs: 5, 2 and Time Over
- Keynote talks – 35 minutes plus 5 min. Q & A
- Oral presentations – 17 minutes 3 min. Q & A
- Panel presentation and Regional reviews -10 minutes each
- Reserved seat for speakers

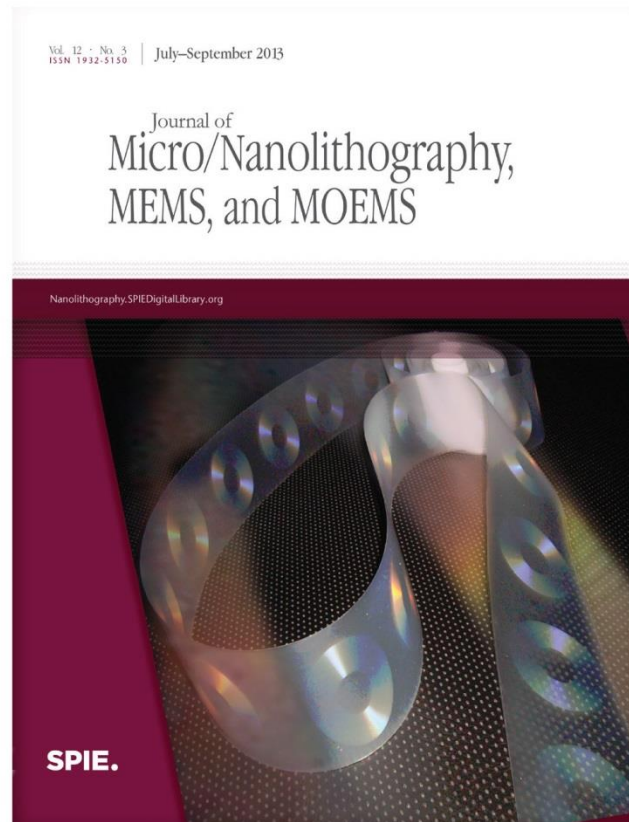
Announcements

- Poster Session (Thursday)
 - Two Best Poster Awards
 - Please use your 3 dots for voting
- EUVL Survey
 - This year we have an audience survey on Thursday afternoon, at the end of the meeting



SPIE

Submit your work to the *Journal of Micro/Nanolithography, MEMS, and MOEMS*

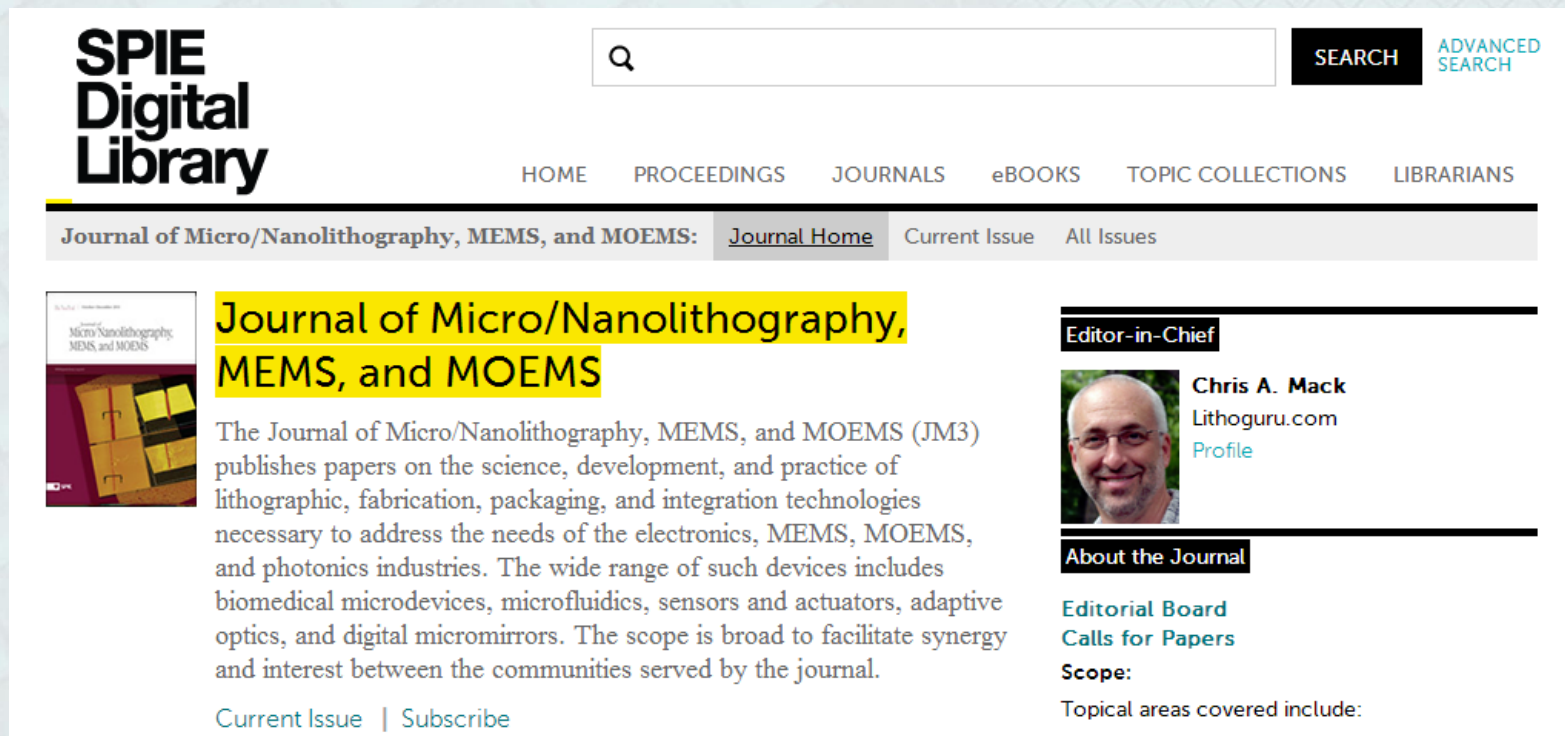


JM³ Scope

- **Lithography:** tools, materials, and processes associated with the patterning of structures that have submicrometer and nanometer-scale features. Included are imaging and nonimaging approaches using optics, electron and other particle beams, nanoimprint, molecular self-assembly, and their hybrids. Applications include semiconductor fabrication, but also patterning for other micro/nanodevices.
- **Microelectromechanical systems (MEMS):** the design, fabrication, operation, reliability, and testing of microdevices that contain both electrical and mechanical elements.
- **Micro-optoelectromechanical systems (MOEMS):** the design, fabrication, operation, reliability, and testing of microdevices that contain electrical, mechanical, and optical elements (that is, the merging of micro-optics and MEMS).
- **Microfabrication:** technologies to shape three-dimensional structures leading to the fabrication of active and passive electronics, photonics, MEMS, MOEMS, micro/nano-optics, and other micro/nanodevices.
- **Metrology:** metrology and process control for the above devices and their fabrication processes.

Where to find JM³ on the web

- Information about the journal, information for contributors, etc:
 - <http://spie.org/x865.xml>
- Submit a manuscript: <http://jm3.msubmit.net/cgi-bin/main.plex>
- Browse, read, and download articles from the SPIE digital library:
 - <http://nanolithography.spiedigitallibrary.org/journal.aspx>



The screenshot shows the SPIE Digital Library website. At the top left is the SPIE Digital Library logo. To its right is a search bar with a magnifying glass icon and a 'SEARCH' button. Further right is a link for 'ADVANCED SEARCH'. Below the logo is a navigation menu with links for HOME, PROCEEDINGS, JOURNALS, eBOOKS, TOPIC COLLECTIONS, and LIBRARIANS. A secondary navigation bar below that highlights 'Journal of Micro/Nanolithography, MEMS, and MOEMS' and includes links for 'Journal Home', 'Current Issue', and 'All Issues'. On the left side, there is a thumbnail image of the journal cover. The main content area features the journal title in large yellow text, followed by a paragraph describing the journal's focus on lithographic, fabrication, packaging, and integration technologies. Below this is a link for 'Current Issue | Subscribe'. On the right side, there is a section for the 'Editor-in-Chief', Chris A. Mack, with a profile picture and a link to his 'Profile'. Below that is a section titled 'About the Journal' with a sub-section 'Editorial Board Calls for Papers' and a 'Scope:' heading, followed by the text 'Topical areas covered include:'. In the bottom right corner, there is a logo for EUV LITHO, INC.

SPIE Digital Library

Q SEARCH ADVANCED SEARCH

HOME PROCEEDINGS JOURNALS eBOOKS TOPIC COLLECTIONS LIBRARIANS


Journal of Micro/Nanolithography, MEMS, and MOEMS: [Journal Home](#) [Current Issue](#) [All Issues](#)

Journal of Micro/Nanolithography, MEMS, and MOEMS

The Journal of Micro/Nanolithography, MEMS, and MOEMS (JM3) publishes papers on the science, development, and practice of lithographic, fabrication, packaging, and integration technologies necessary to address the needs of the electronics, MEMS, MOEMS, and photonics industries. The wide range of such devices includes biomedical microdevices, microfluidics, sensors and actuators, adaptive optics, and digital micromirrors. The scope is broad to facilitate synergy and interest between the communities served by the journal.

[Current Issue](#) | [Subscribe](#)

Editor-in-Chief

 **Chris A. Mack**
Lithoguru.com
[Profile](#)

About the Journal

Editorial Board Calls for Papers

Scope:
Topical areas covered include:

EUV LITHO, INC.

WORKSHOP AGENDA

- **8:40 AM ...Session 1: Keynote Presentations**
- **10:00 AMBreak (20 Minutes)**
- **10:20 AM..... Session 2: EUV Sources**
- **12:00 PM.....Lunch**

WORKSHOP AGENDA

- **1:00 PMSession 3: Regional Reviews**
- **1:50 PMBreak (20 Minutes)**
- **2:10 PMSession 4: Optics
(On Agenda as 2:30 PM)**
- **3:50 PM.....Adjourn for the day**